

# Anjana Devi

## List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

209  
papers

4,089  
citations

35  
h-index

51  
g-index

227  
ext. papers

4,593  
ext. citations

4.8  
avg, IF

5.24  
L-index

#	Paper	IF	Citations
209	Ferromagnetic Europium Sulfide Thin Films: Influence of Precursors on Magneto-Optical Properties. <i>Chemistry of Materials</i> , <b>2022</b> , 34, 152-164	9.6	0
208	Highly sensitive and stable MEMS acetone sensors based on well-designed FeO/C mesoporous nanorods.. <i>Journal of Colloid and Interface Science</i> , <b>2022</b> , 622, 156-168	9.3	2
207	Co(II) Amide, Pyrrolate, and Aminopyridinate Complexes: Assessment of their Manifold Structural Chemistry and Thermal Properties**. <i>European Journal of Inorganic Chemistry</i> , <b>2021</b> , 2021, 5119	2.3	0
206	Investigation of an atomic-layer-deposited Al <sub>2</sub> O <sub>3</sub> diffusion barrier between Pt and Si for the use in atomic scale atom probe tomography studies on a combinatorial processing platform. <i>Surface and Interface Analysis</i> , <b>2021</b> , 53, 727-733	1.5	
205	(tBuN)SiMe <sub>2</sub> NMe <sub>2</sub> a new N,N'-di-monoanionic ligand for atomic layer deposition precursors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2021</b> , 39, 032409	2.9	0
204	Cobalt Metal ALD: Understanding the Mechanism and Role of Zinc Alkyl Precursors as Reductants for Low-Resistivity Co Thin Films. <i>Chemistry of Materials</i> , <b>2021</b> , 33, 5045-5057	9.6	3
203	Rational Development of Guanidinate and Amidinate Based Cerium and Ytterbium Complexes as Atomic Layer Deposition Precursors: Synthesis, Modeling, and Application. <i>Chemistry - A European Journal</i> , <b>2021</b> , 27, 4913-4926	4.8	3
202	Atomic layer deposition of dielectric YO thin films from a homoleptic yttrium formamidinate precursor and water.. <i>RSC Advances</i> , <b>2021</b> , 11, 2565-2574	3.7	7
201	Fabrication of GdxFeyOz films using an atomic layer deposition-type approach. <i>CrystEngComm</i> , <b>2021</b> , 23, 730-740	3.3	0
200	A study on the influence of ligand variation on formamidinate complexes of yttrium: new precursors for atomic layer deposition of yttrium oxide. <i>Dalton Transactions</i> , <b>2021</b> , 50, 12944-12956	4.3	1
199	Direct liquid injection chemical vapor deposition of ZrO <sub>2</sub> films from a heteroleptic Zr precursor: interplay between film characteristics and corrosion protection of stainless steel. <i>Journal of Materials Research and Technology</i> , <b>2021</b> , 13, 1599-1614	5.5	3
198	Chemical Vapor Deposition of Cobalt and Nickel Ferrite Thin Films: Investigation of Structure and Pseudocapacitive Properties. <i>Advanced Materials Interfaces</i> , <b>2021</b> , 8, 2100949	4.6	0
197	Facile Chemical Route to Prepare Water Soluble Epitaxial Sr <sub>3</sub> Al <sub>2</sub> O <sub>6</sub> Sacrificial Layers for Free-Standing Oxides. <i>Advanced Materials Interfaces</i> , <b>2021</b> , 8, 2001643	4.6	4
196	CVD grown GaSbN films as visible-light active photoanodes. <i>Dalton Transactions</i> , <b>2021</b> , 50, 14832-14841	4.3	
195	Sensing and electrocatalytic activity of tungsten disulphide thin films fabricated via metalorganic chemical vapour deposition. <i>Journal of Materials Chemistry C</i> , <b>2021</b> , 9, 10254-10265	7.1	0
194	A Rare Low-Spin Co Bis(βilyldiamide) with High Thermal Stability: Steric Enforcement of a Doublet Configuration. <i>Angewandte Chemie - International Edition</i> , <b>2020</b> , 59, 14138-14142	16.4	6
193	Hierarchical highly ordered SnO nanobowl branched ZnO nanowires for ultrasensitive and selective hydrogen sulfide gas sensing. <i>Microsystems and Nanoengineering</i> , <b>2020</b> , 6, 30	7.7	19

192	Additive-free spin coating of tin oxide thin films: synthesis, characterization and evaluation of tin Eketoiminates as a new precursor class for solution deposition processes. <i>Dalton Transactions</i> , <b>2020</b> , 49, 10755-10764	4.3	2
191	Tuning Coordination Geometry of Nickel Ketoiminates and Its Influence on Thermal Characteristics for Chemical Vapor Deposition of Nanostructured NiO Electrocatalysts. <i>Inorganic Chemistry</i> , <b>2020</b> , 59, 10059-10070	5.1	5
190	Atomic scale growth of GdFeO <sub>3</sub> perovskite thin films. <i>Thin Solid Films</i> , <b>2020</b> , 698, 137848	2.2	7
189	From Precursor Chemistry to Gas Sensors: Plasma-Enhanced Atomic Layer Deposition Process Engineering for Zinc Oxide Layers from a Nonpyrophoric Zinc Precursor for Gas Barrier and Sensor Applications. <i>Small</i> , <b>2020</b> , 16, e1907506	11	7
188	Comparative Study of Photocatalytic Dynamics in CVD-deposited CuWO <sub>4</sub> , CuO, and WO <sub>3</sub> Thin Films for Photoelectrocatalysis. <i>Zeitschrift Fur Physikalische Chemie</i> , <b>2020</b> , 234, 699-717	3.1	9
187	A carbene stabilized precursor for the spatial atomic layer deposition of copper thin films. <i>Chemical Communications</i> , <b>2020</b> , 56, 13752-13755	5.8	3
186	Ein seltenes Low-Spin-CoIV-Bis(Ebilyldiamid) mit hoher thermischer Stabilität Sterische Erzwingung einer Dublett Konfiguration. <i>Angewandte Chemie</i> , <b>2020</b> , 132, 14242-14246	3.6	0
185	A new metalorganic chemical vapor deposition process for MoS <sub>2</sub> with a 1,4-diazabutadienyl stabilized molybdenum precursor and elemental sulfur. <i>Dalton Transactions</i> , <b>2020</b> , 49, 13462-13474	4.3	8
184	Study on Structural and Thermal Characteristics of Heteroleptic Yttrium Complexes as Potential Precursors for Vapor Phase Deposition. <i>European Journal of Inorganic Chemistry</i> , <b>2020</b> , 2020, 3587-3596	2.3	9
183	Up-converting ALD/MLD thin films with Yb <sup>3+</sup> , Er <sup>3+</sup> in amorphous organic framework. <i>Journal of Luminescence</i> , <b>2019</b> , 213, 310-315	3.8	10
182	Potential Precursor Alternatives to the Pyrophoric Trimethylaluminium for the Atomic Layer Deposition of Aluminium Oxide. <i>Chemistry - A European Journal</i> , <b>2019</b> , 25, 7489-7500	4.8	5
181	Fabrication of heterostructured p-CuO/n-SnO <sub>2</sub> core-shell nanowires for enhanced sensitive and selective formaldehyde detection. <i>Sensors and Actuators B: Chemical</i> , <b>2019</b> , 290, 233-241	8.5	64
180	How water flips at charged titanium dioxide: an SFG-study on the water-TiO interface. <i>Physical Chemistry Chemical Physics</i> , <b>2019</b> , 21, 8956-8964	3.6	7
179	PEALD of HfO Thin Films: Precursor Tuning and a New Near-Ambient-Pressure XPS Approach to in Situ Examination of Thin-Film Surfaces Exposed to Reactive Gases. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2019</b> , 11, 28407-28422	9.5	8
178	Monitoring Surface Stoichiometry, Work Function and Valance Band of Tungsten Oxide (WO <sub>3</sub> ), Molybdenum Oxide (MoO <sub>3</sub> ) and Tin Oxide (SnO <sub>2</sub> ) Thin Films as a Function of Temperature and Oxygen Partial Pressure with Advanced Surface Sensitive Techniques for Chemical Sensing Applications. <i>Proceedings (mdpi)</i> , <b>2019</b> , 14, 27	0.3	1
177	Atomic layer deposition of functional multicomponent oxides. <i>APL Materials</i> , <b>2019</b> , 7, 110901	5.7	24
176	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of Tin(IV) Oxide from a Functionalized Alkyl Precursor: Fabrication and Evaluation of SnO-Based Thin-Film Transistor Devices. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2019</b> , 11, 3169-3180	9.5	22
175	Luminescent NdS thin films: a new chemical vapour deposition route towards rare-earth sulphides. <i>Dalton Transactions</i> , <b>2019</b> , 48, 2926-2938	4.3	4

174	Investigating Zinc Ketoiminates as a New Class of Precursors for Solution Deposition of ZnO Thin Films. <i>Journal of Nanoscience and Nanotechnology</i> , <b>2019</b> , 19, 867-876	1.3	3
173	Validation of a Terminally Amino Functionalized Tetra-Alkyl Sn(IV) Precursor in Metal Organic Chemical Vapor Deposition of SnO <sub>2</sub> Thin Films: Study of Film Growth Characteristics, Optical, and Electrical Properties. <i>Advanced Materials Interfaces</i> , <b>2019</b> , 6, 1801540	4.6	6
172	CVD-grown copper tungstate thin films for solar water splitting. <i>Journal of Materials Chemistry A</i> , <b>2018</b> , 6, 10206-10216	13	17
171	Rational Development of Cobalt Ketoiminate Complexes: Alternative Precursors for Vapor-Phase Deposition of Spinel Cobalt Oxide Photoelectrodes. <i>Inorganic Chemistry</i> , <b>2018</b> , 57, 5133-5144	5.1	10
170	Ultrasound-mediated deposition and cytocompatibility of apatite-like coatings on magnesium alloys. <i>Surface and Coatings Technology</i> , <b>2018</b> , 345, 167-176	4.4	2
169	PEALD of SiO <sub>2</sub> and AlO <sub>x</sub> Thin Films on Polypropylene: Investigations of the Film Growth at the Interface, Stress, and Gas Barrier Properties of Dyads. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2018</b> , 10, 7422-7434	9.5	22
168	Manganese(II) Molecular Sources for Plasma-Assisted CVD of Mn Oxides and Fluorides: From Precursors to Growth Process. <i>Journal of Physical Chemistry C</i> , <b>2018</b> , 122, 1367-1375	3.8	29
167	Molecular engineering of Ga-ketoiminates: synthesis, structure and evaluation as precursors for the additive-free spin-coated deposition of gallium oxide thin films. <i>New Journal of Chemistry</i> , <b>2018</b> , 42, 3196-3210 <sup>5</sup>	2.6	10
166	Fabrication of zinc-dicarboxylate- and zinc-pyrazolate-carboxylate-framework thin films through vapour-solid deposition. <i>Dalton Transactions</i> , <b>2018</b> , 47, 14179-14183	4.3	11
165	Tailored Ketoiminate Complexes of Iron: Synthesis, Characterization, and Evaluation towards Solution-Based Deposition of Iron Oxide Thin Films. <i>European Journal of Inorganic Chemistry</i> , <b>2018</b> , 2018, 1824-1833	2.3	7
164	Direct Growth of MoS <sub>2</sub> and WS <sub>2</sub> Layers by Metal Organic Chemical Vapor Deposition. <i>Advanced Materials Interfaces</i> , <b>2018</b> , 5, 1800140	4.6	34
163	A combinatorial approach to enhance barrier properties of thin films on polymers: Seeding and capping of PECVD thin films by PEALD. <i>Plasma Processes and Polymers</i> , <b>2018</b> , 15, 1700209	3.4	7
162	Water assisted atomic layer deposition of yttrium oxide using tris(2-diisopropyl-2-dimethylamido-guanidinato) yttrium(iii): process development, film characterization and functional properties.. <i>RSC Advances</i> , <b>2018</b> , 8, 4987-4994	3.7	23
161	Synthesis of rare-earth metal and rare-earth metal-fluoride nanoparticles in ionic liquids and propylene carbonate. <i>Beilstein Journal of Nanotechnology</i> , <b>2018</b> , 9, 1881-1894	3	14
160	Atomic Layer Deposition of Nickel on ZnO Nanowire Arrays for High-Performance Supercapacitors. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2018</b> , 10, 468-476	9.5	20
159	Atomic/molecular layer deposition of Cu-organic thin films. <i>Dalton Transactions</i> , <b>2018</b> , 47, 15791-15800	4.3	12
158	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. <i>Chemistry of Materials</i> , <b>2018</b> , 30, 8690-8701	9.6	16
157	Ein N-heterocyclischer Carbenkomplex des Silbers für die plasmaunterstützte räumlich getrennte Atomlagenabscheidung dünner Silberschichten bei Atmosphärendruck. <i>Angewandte Chemie</i> , <b>2018</b> , 130, 16458-16462	3.6	1

156	An N-Heterocyclic Carbene Based Silver Precursor for Plasma-Enhanced Spatial Atomic Layer Deposition of Silver Thin Films at Atmospheric Pressure. <i>Angewandte Chemie - International Edition</i> , <b>2018</b> , 57, 16224-16227	16.4	13
155	Designing Stability into Thermally Reactive Plumblyenes. <i>Inorganic Chemistry</i> , <b>2018</b> , 57, 8218-8226	5.1	11
154	Transport mechanisms through PE-CVD coatings: influence of temperature, coating properties and defects on permeation of water vapour. <i>Journal Physics D: Applied Physics</i> , <b>2017</b> , 50, 085203	3	2
153	Synthesis and evaluation of new copper ketoiminate precursors for a facile and additive-free solution-based approach to nanoscale copper oxide thin films. <i>Dalton Transactions</i> , <b>2017</b> , 46, 2670-2679	4.3	15
152	Photoactive Zinc Ferrites Fabricated via Conventional CVD Approach. <i>ACS Sustainable Chemistry and Engineering</i> , <b>2017</b> , 5, 2917-2926	8.3	28
151	Atomic/molecular layer deposition of hybrid inorganic/organic thin films from erbium guanidinate precursor. <i>Journal of Materials Science</i> , <b>2017</b> , 52, 6216-6224	4.3	13
150	Nanostructured Fe <sub>2</sub> O <sub>3</sub> Processing via Water-Assisted ALD and Low-Temperature CVD from a Versatile Iron Ketoiminate Precursor. <i>Advanced Materials Interfaces</i> , <b>2017</b> , 4, 1700155	4.6	20
149	Influence of PE-CVD and PE-ALD on defect formation in permeation barrier films on PET and correlation to atomic oxygen fluence. <i>Journal Physics D: Applied Physics</i> , <b>2017</b> , 50, 235201	3	7
148	Spectroscopic investigation of wheat grains ( <i>Triticum aestivum</i> ) infected by wheat seed gall nematodes ( <i>Anguina tritici</i> ). <i>Biocatalysis and Agricultural Biotechnology</i> , <b>2017</b> , 9, 58-66	4.2	9
147	New amidinate complexes of indium(iii): promising CVD precursors for transparent and conductive InO thin films. <i>Dalton Transactions</i> , <b>2017</b> , 46, 10220-10231	4.3	18
146	Review Article: Recommended reading list of early publications on atomic layer deposition Outcome of the Virtual Project on the History of ALD <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2017</b> , 35, 010801	2.9	55
145	Unearthing [3-(Dimethylamino)propyl]aluminium(III) Complexes as Novel Atomic Layer Deposition (ALD) Precursors for Al <sub>2</sub> O <sub>3</sub> : Synthesis, Characterization and ALD Process Development. <i>Chemistry - A European Journal</i> , <b>2017</b> , 23, 10768-10772	4.8	12
144	Integrating AlN with GdN Thin Films in an in Situ CVD Process: Influence on the Oxidation and Crystallinity of GdN. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2017</b> , 9, 27036-27044	9.5	7
143	Low temperature growth of gallium oxide thin films via plasma enhanced atomic layer deposition. <i>Dalton Transactions</i> , <b>2017</b> , 46, 16551-16561	4.3	37
142	Molecular Engineering of Mn Diamine Diketonate Precursors for the Vapor Deposition of Manganese Oxide Nanostructures. <i>Chemistry - A European Journal</i> , <b>2017</b> , 23, 17954-17963	4.8	27
141	Low-Temperature Atomic Layer Deposition of Low-Resistivity Copper Thin Films Using Cu(dmap) <sub>2</sub> and Tertiary Butyl Hydrazine. <i>Chemistry of Materials</i> , <b>2017</b> , 29, 6502-6510	9.6	18
140	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. <i>Chemistry of Materials</i> , <b>2017</b> , 29, 5796-5805	9.6	32
139	Effects of Post Annealing Treatments on the Interfacial Chemical Properties and Band Alignment of AlN/Si Structure Prepared by Atomic Layer Deposition. <i>Nanoscale Research Letters</i> , <b>2017</b> , 12, 102	5	10

138	A cobalt(ii)heteroarylalkenolate precursor for homogeneous CoO coatings by atomic layer deposition. <i>Dalton Transactions</i> , <b>2017</b> , 46, 12996-13001	4.3	8
137	Temperature-dependent transport mechanisms through PE-CVD coatings: comparison of oxygen and water vapour. <i>Journal Physics D: Applied Physics</i> , <b>2017</b> , 50, 395302	3	2
136	Analysis of dispersive interactions at polymer/TiAlN interfaces by means of dynamic force spectroscopy. <i>Physical Chemistry Chemical Physics</i> , <b>2017</b> , 20, 180-190	3.6	5
135	Letters From Our Readers. <i>Angle Orthodontist</i> , <b>2016</b> , 86, 1058	2.6	
134	Rapid palatal expansion, with and without alternating constriction. <i>American Journal of Orthodontics and Dentofacial Orthopedics</i> , <b>2016</b> , 149, 779-80	2.1	
133	An efficient PE-ALD process for TiO <sub>2</sub> thin films employing a new Ti-precursor. <i>Journal of Materials Chemistry C</i> , <b>2016</b> , 4, 1057-1065	7.1	22
132	Systematic molecular engineering of Zn-ketoiminates for application as precursors in atomic layer depositions of zinc oxide. <i>Dalton Transactions</i> , <b>2016</b> , 45, 19012-19023	4.3	12
131	Ideal parameter to assess efficacy of fixed functional appliance: angular or linear?. <i>European Journal of Orthodontics</i> , <b>2016</b> , 38, 337	3.3	
130	MOCVD of TiO <sub>2</sub> thin films from a modified titanium alkoxide precursor. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2015</b> , 212, 1563-1570	1.6	7
129	Metal-organic CVD of Y <sub>2</sub> O <sub>3</sub> Thin Films using Yttrium tris-amidinates . <i>Chemical Vapor Deposition</i> , <b>2015</b> , 21, 335-342		7
128	Electrical and optical properties of TiO <sub>2</sub> thin films prepared by plasma-enhanced atomic layer deposition. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2014</b> , 211, 416-424	1.6	34
127	Tailoring iron(III) oxide nanomorphology by chemical vapor deposition: Growth and characterization. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2014</b> , 211, 316-322	1.6	12
126	Low Temperature Stabilization of Nanoscale Epitaxial Spinel Ferrite Thin Films by Atomic Layer Deposition. <i>Advanced Functional Materials</i> , <b>2014</b> , 24, 5368-5374	15.6	36
125	Novel $\beta$ -ketoiminato complexes of zirconium: synthesis, characterization and evaluation for solution based processing of ZrO <sub>2</sub> thin films. <i>Dalton Transactions</i> , <b>2014</b> , 43, 2384-96	4.3	6
124	Indium-tris-guanidinate: a promising class of precursors for water assisted atomic layer deposition of In <sub>2</sub> O <sub>3</sub> thin films. <i>Dalton Transactions</i> , <b>2014</b> , 43, 937-40	4.3	23
123	Atomic Layer Deposition of TiO <sub>2</sub> and ZrO <sub>2</sub> Thin Films Using Heteroleptic Guanidinate Precursors. <i>Chemical Vapor Deposition</i> , <b>2014</b> , 20, 209-216		5
122	Recent Advances Using Guanidinate Ligands for Chemical Vapour Deposition (CVD) and Atomic Layer Deposition (ALD) Applications. <i>Australian Journal of Chemistry</i> , <b>2014</b> , 67, 989	1.2	25
121	Nanostructured Er <sub>2</sub> O <sub>3</sub> thin films grown by metalorganic chemical vapour deposition. <i>Journal of Nanoscience and Nanotechnology</i> , <b>2014</b> , 14, 5095-102	1.3	5

120	Atomic-scale engineering of multifunctional nano-sized materials and films. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2014</b> , 211, 249-250	1.6	
119	MOCVD of TiO <sub>2</sub> Thin Films using a Heteroleptic Titanium Complex: Precursor Evaluation and Investigation of Optical, Photoelectrochemical and Electrical Properties. <i>Chemical Vapor Deposition</i> , <b>2014</b> , 20, 224-233		4
118	Surface Decoration of $\gamma$ -Fe <sub>2</sub> O <sub>3</sub> Nanorods by CuO Via a Two-Step CVD/Sputtering Approach**. <i>Chemical Vapor Deposition</i> , <b>2014</b> , 20, 313-319		10
117	MOCVD of tungsten nitride thin films: Comparison of precursor performance and film characteristics. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2014</b> , 211, 260-266	1.6	7
116	Investigation of Optical, Electrical, and Mechanical Properties of MOCVD-grown ZrO <sub>2</sub> Films. <i>Chemical Vapor Deposition</i> , <b>2014</b> , 20, 320-327		6
115	Growth and Crystallization of TiO <sub>2</sub> Thin Films by Atomic Layer Deposition Using a Novel Amido Guanidinate Titanium Source and Tetrakis-dimethylamido-titanium. <i>Chemistry of Materials</i> , <b>2013</b> , 25, 2934-2943	9.6	65
114	Old Chemistries for new applications: Perspectives for development of precursors for MOCVD and ALD applications. <i>Coordination Chemistry Reviews</i> , <b>2013</b> , 257, 3332-3384	23.2	106
113	Atomic layer deposition of Er <sub>2</sub> O <sub>3</sub> thin films from Er tris-guanidinate and water: process optimization, film analysis and electrical properties. <i>Journal of Materials Chemistry C</i> , <b>2013</b> , 1, 3939	7.1	16
112	Transition metal nitride thin films grown by MOCVD using amidinato based complexes [M(NtBu) <sub>2</sub> {(iPrN) <sub>2</sub> CMe <sub>2</sub> }] (M = Mo, W) as precursors. <i>Surface and Coatings Technology</i> , <b>2013</b> , 230, 130-136	4.4	19
111	A Z <sub>7</sub> = 6 crystal structure of (E)-N,N'-dicyclohexylacetamide. <i>Journal of Molecular Structure</i> , <b>2013</b> , 1031, 239-245	3.4	3
110	Homoleptic gadolinium amidinates as precursors for MOCVD of oriented gadolinium nitride (GdN) thin films. <i>Inorganic Chemistry</i> , <b>2013</b> , 52, 286-96	5.1	22
109	[Zr(NEtMe) <sub>2</sub> (guan-NEtMe) <sub>2</sub> ] as a Novel Atomic Layer Deposition Precursor: ZrO <sub>2</sub> Film Growth and Mechanistic Studies. <i>Chemistry of Materials</i> , <b>2013</b> , 25, 3088-3095	9.6	16
108	Intrinsic Nitrogen-doped CVD-grown TiO <sub>2</sub> Thin Films from All-N-coordinated Ti Precursors for Photoelectrochemical Applications. <i>Chemical Vapor Deposition</i> , <b>2013</b> , 19, 45-52		32
107	Rare-earth substituted HfO <sub>2</sub> thin films grown by metalorganic chemical vapor deposition. <i>Thin Solid Films</i> , <b>2012</b> , 520, 4512-4517	2.2	9
106	Atomic Layer Deposition of HfO <sub>2</sub> Thin Films Employing a Heteroleptic Hafnium Precursor. <i>Chemical Vapor Deposition</i> , <b>2012</b> , 18, 27-35		16
105	Strain-induced phase transitions in epitaxial NaNbO <sub>3</sub> thin films grown by metalorganic chemical vapour deposition. <i>Journal of Applied Crystallography</i> , <b>2012</b> , 45, 1015-1023	3.8	32
104	Design, synthesis and antimicrobial evaluation of novel 1-benzyl 2-butyl-4-chloroimidazole embodied 4-azafluorenones via molecular hybridization approach. <i>Bioorganic and Medicinal Chemistry Letters</i> , <b>2012</b> , 22, 7475-80	2.9	31
103	Influence of process parameters on the crystallinity, morphology and composition of tungsten oxide-based thin films grown by metalorganic chemical vapor deposition. <i>Thin Solid Films</i> , <b>2012</b> , 522, 11-16	2.2	11

102	Fe <sub>2</sub> O <sub>3</sub> nanomaterials from an iron(II) diketone-diamine complex: a study from molecular precursor to growth process. <i>Dalton Transactions</i> , <b>2012</b> , 41, 149-55	4.3	57
101	Sc <sub>2</sub> O <sub>3</sub> , Er <sub>2</sub> O <sub>3</sub> , and Y <sub>2</sub> O <sub>3</sub> thin films by MOCVD from volatile guanidinate class of rare-earth precursors. <i>Dalton Transactions</i> , <b>2012</b> , 41, 13936-47	4.3	35
100	Microgradient-heaters as tools for high-throughput experimentation. <i>ACS Combinatorial Science</i> , <b>2012</b> , 14, 531-6	3.9	2
99	Fabrication of ZrO <sub>2</sub> and ZrN Films by Metalorganic Chemical Vapor Deposition Employing New Zr Precursors. <i>Crystal Growth and Design</i> , <b>2012</b> , 12, 5079-5089	3.5	24
98	Atomic Layer Deposition of Gd <sub>2</sub> O <sub>3</sub> and Dy <sub>2</sub> O <sub>3</sub> : A Study of the ALD Characteristics and Structural and Electrical Properties. <i>Chemistry of Materials</i> , <b>2012</b> , 24, 651-658	9.6	38
97	Ag/ZnO nanomaterials as high performance sensors for flammable and toxic gases. <i>Nanotechnology</i> , <b>2012</b> , 23, 025502	3.4	42
96	Surfactant-Induced Nonhydrolytic Synthesis of Phase-Pure ZrO <sub>2</sub> Nanoparticles from MetalOrganic and Oxocluster Precursors. <i>Chemistry of Materials</i> , <b>2012</b> , 24, 4274-4282	9.6	20
95	Co <sub>3</sub> O <sub>4</sub> /ZnO nanocomposites: from plasma synthesis to gas sensing applications. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2012</b> , 4, 928-34	9.5	125
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91	Atomic vapor deposition approach to In <sub>2</sub> O <sub>3</sub> thin films. <i>Journal of Nanoscience and Nanotechnology</i> , <b>2011</b> , 11, 8094-100	1.3	7
90	Growth of epitaxial sodium-bismuth-titanate films by metal-organic chemical vapor phase deposition. <i>Thin Solid Films</i> , <b>2011</b> , 520, 239-244	2.2	9
89	Plasma enhanced-CVD of undoped and fluorine-doped Co <sub>3</sub> O <sub>4</sub> nanosystems for novel gas sensors. <i>Sensors and Actuators B: Chemical</i> , <b>2011</b> , 160, 79-86	8.5	50
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81	p-Co <sub>3</sub> O <sub>4</sub> /n-ZnO, Obtained by PECVD, Analyzed by X-ray Photoelectron Spectroscopy. <i>Surface Science Spectra</i> , <b>2011</b> , 18, 36-45	1.2	6
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78	Downscaling of defect-passivated Gd <sub>2</sub> O <sub>3</sub> thin films on p-Si(0 0 1) wafers grown by H <sub>2</sub> O-assisted atomic layer deposition. <i>Semiconductor Science and Technology</i> , <b>2010</b> , 25, 105001	1.8	6
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